

Current Status of Development of XFEL Optics in Japan

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SCSS/SPring-8/JASRI/RIKEN

*2nd meeting on Future XFEL optics:
“Damage threshold of Mirrors and Multilayers”
@ Prague, Nov. 23, 2006*

Collaborators

Diamond crystal: K. Tamasaku, Y. Shimizu, H. Sumiya (Sumitomo Electric Industry)

Beryllium window: S. Goto

X-ray Mirror: K. Yamauchi, H. Mimura, S. Matsuyama, H. Yumoto, ...
(Osaka Univ.)

& SCSS team



Contents

1. XFEL project at Japan
2. Dose estimation
2. Optics development at SPring-8



SPring-8

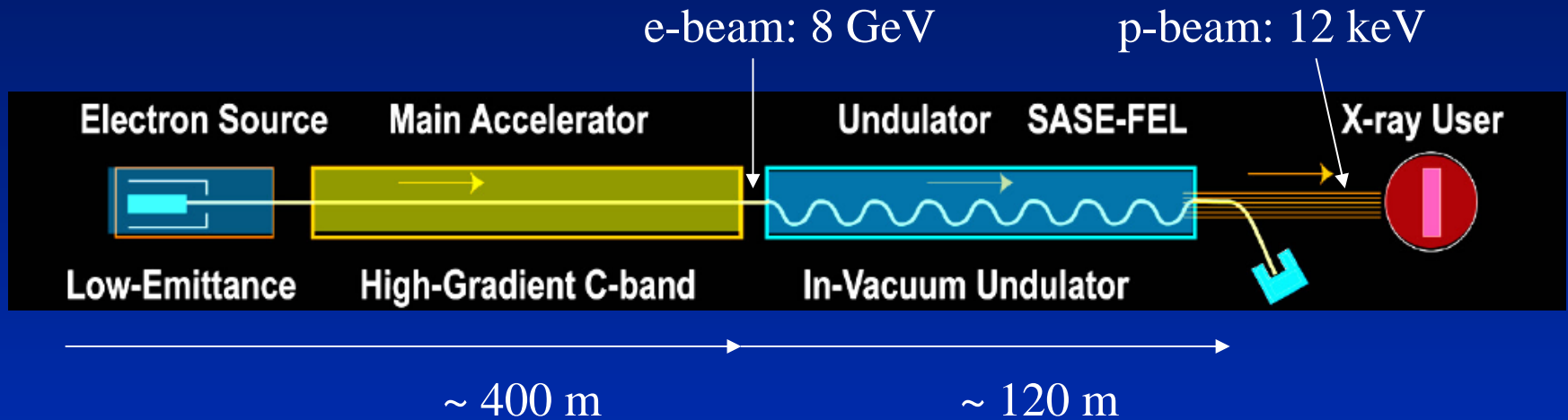
SPring-8 (1436 m)
since 1997

XFEL (700 m)
from ~2011



XFEL at Japan

(SCSS: SPring-8 Compact SASE Source)



e-gun

Main linac

Undulator

SCSS: DC thermionic

Normal-conducting C-band

In-vacuum short period

Not RF-photocathode

Not Superconducting

Not out-of vacuum

Not L-band

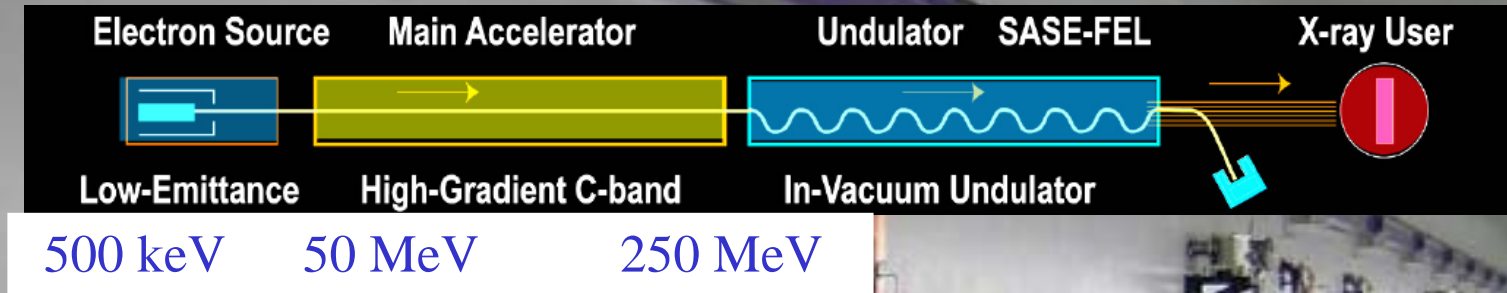
SPring-8

SPring-8 (1436 m)
since 1997

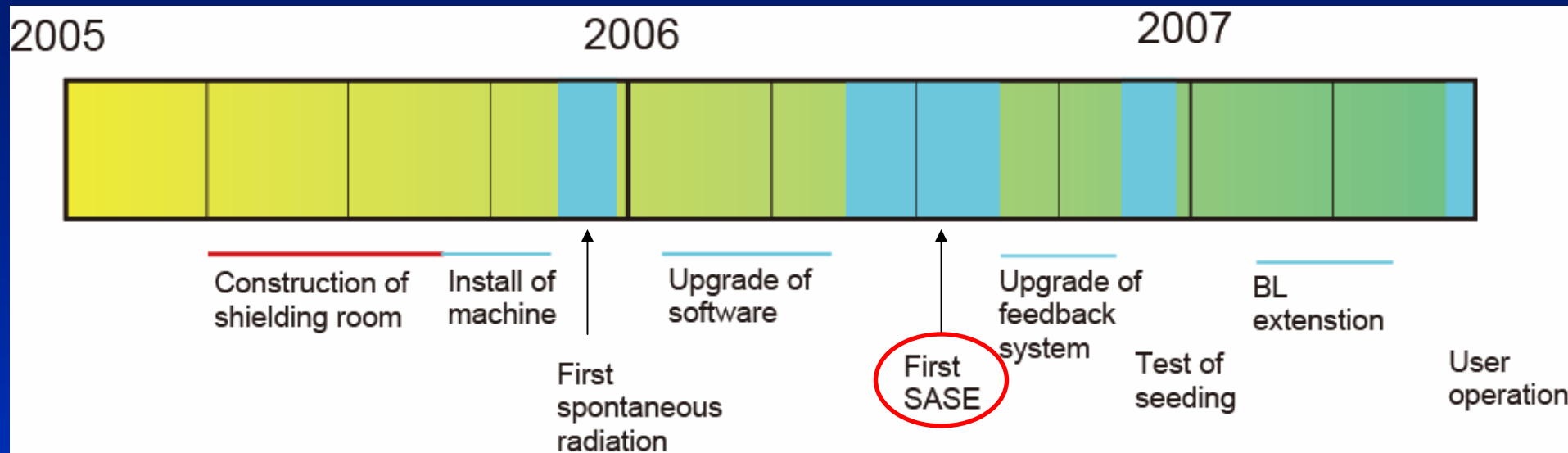
XFEL (700 m)
from ~2011



SCSS Prototype Accelerator (250 MeV, $\lambda \sim 50$ nm) Construction in 2005

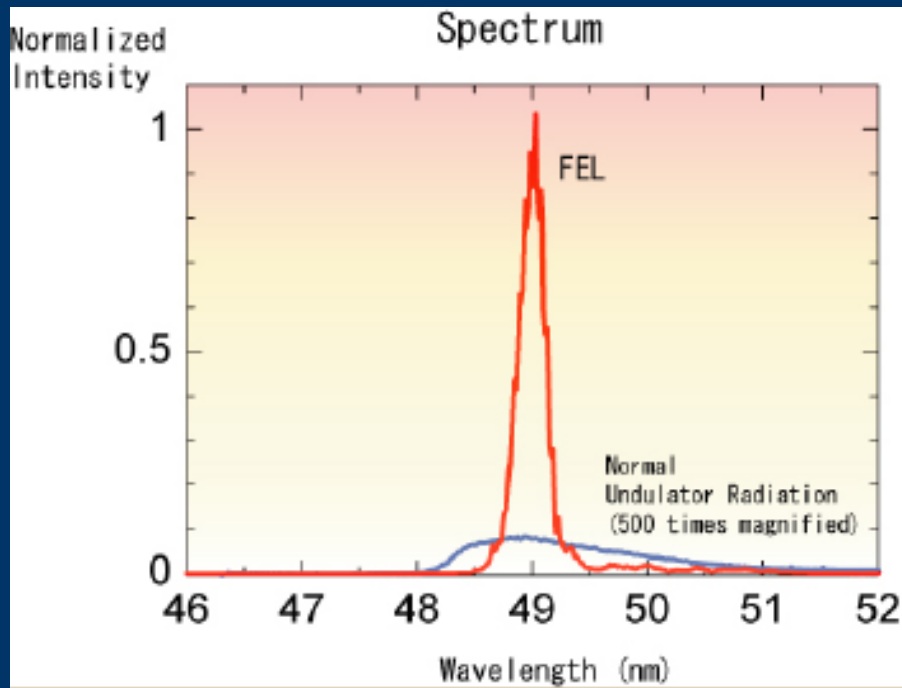


Schedule summary

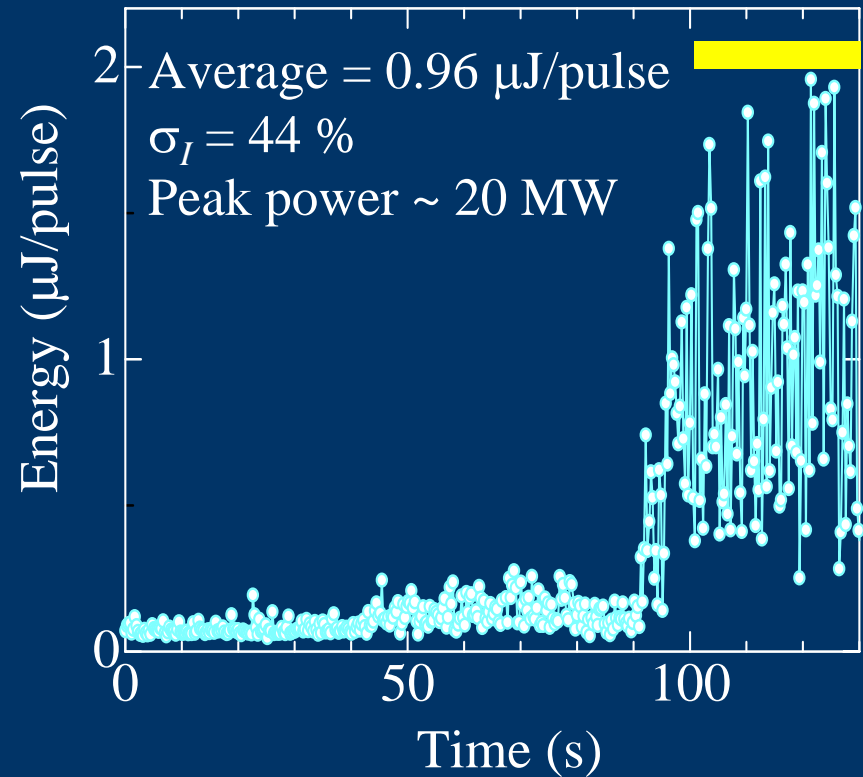


First Lasing (June, 2006)

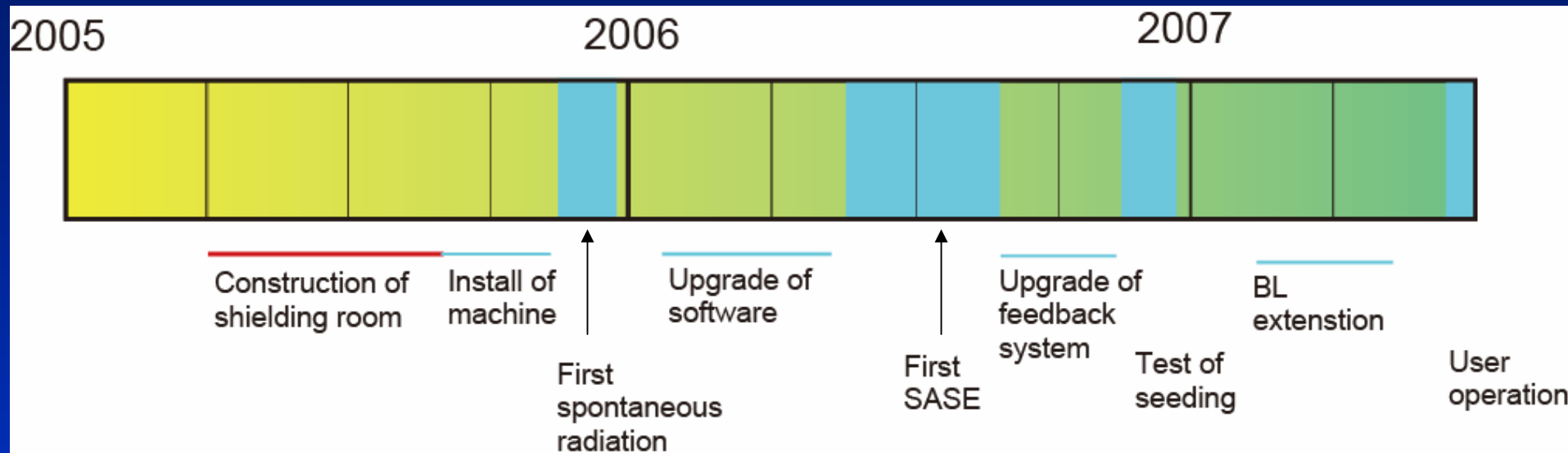
Energy Spectrum



Pulse Energy



Schedule summary



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XFEL: construction of machine building

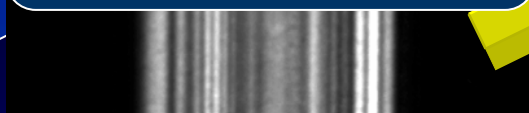
Photon Optics for XFEL



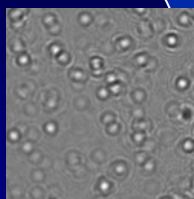
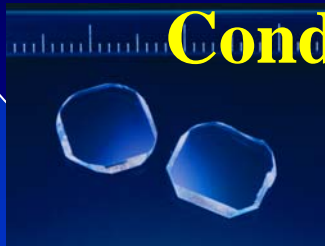
XFEL



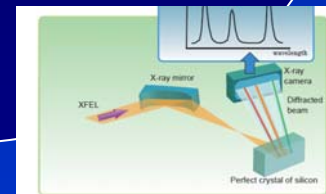
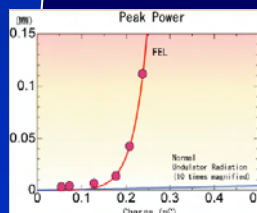
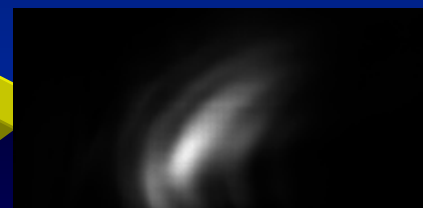
**Dose
Spatial coherence**



**Photon Beam
Conditioning**



**Photon Beam
Diagnostics**



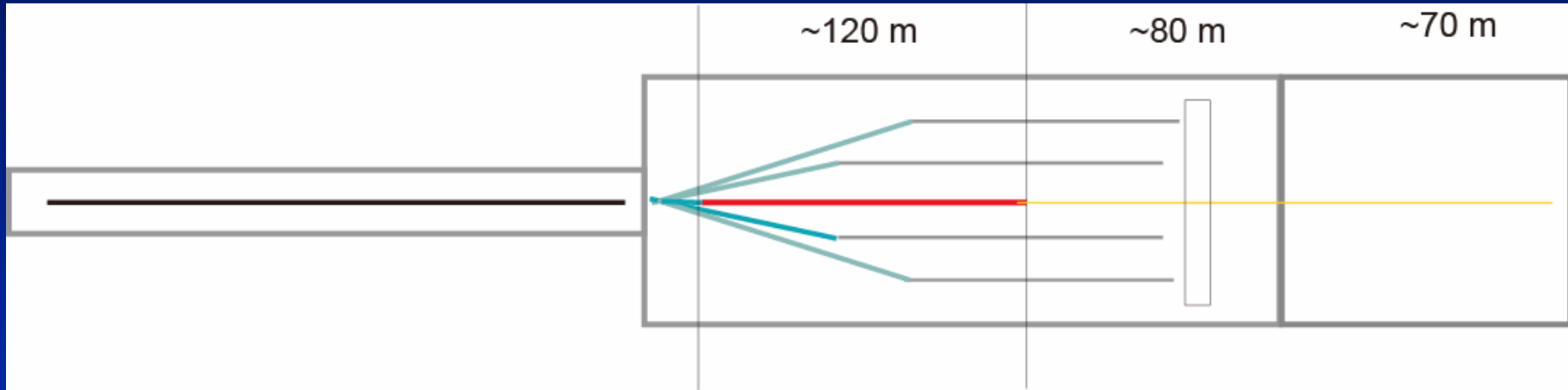
3rd gen. SR



VUV FEL



Plan of 8 GeV machine



Accelerator tunnel

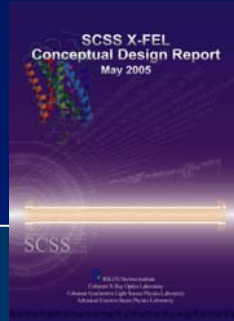
Undulator tunnel

Exp. hall

Repetition rate of 60 Hz: No need for considering thermal issue

Typical length from source: ~ 100 m

Dose for normal incidence



Parameters:

7.6e11 photons/pls

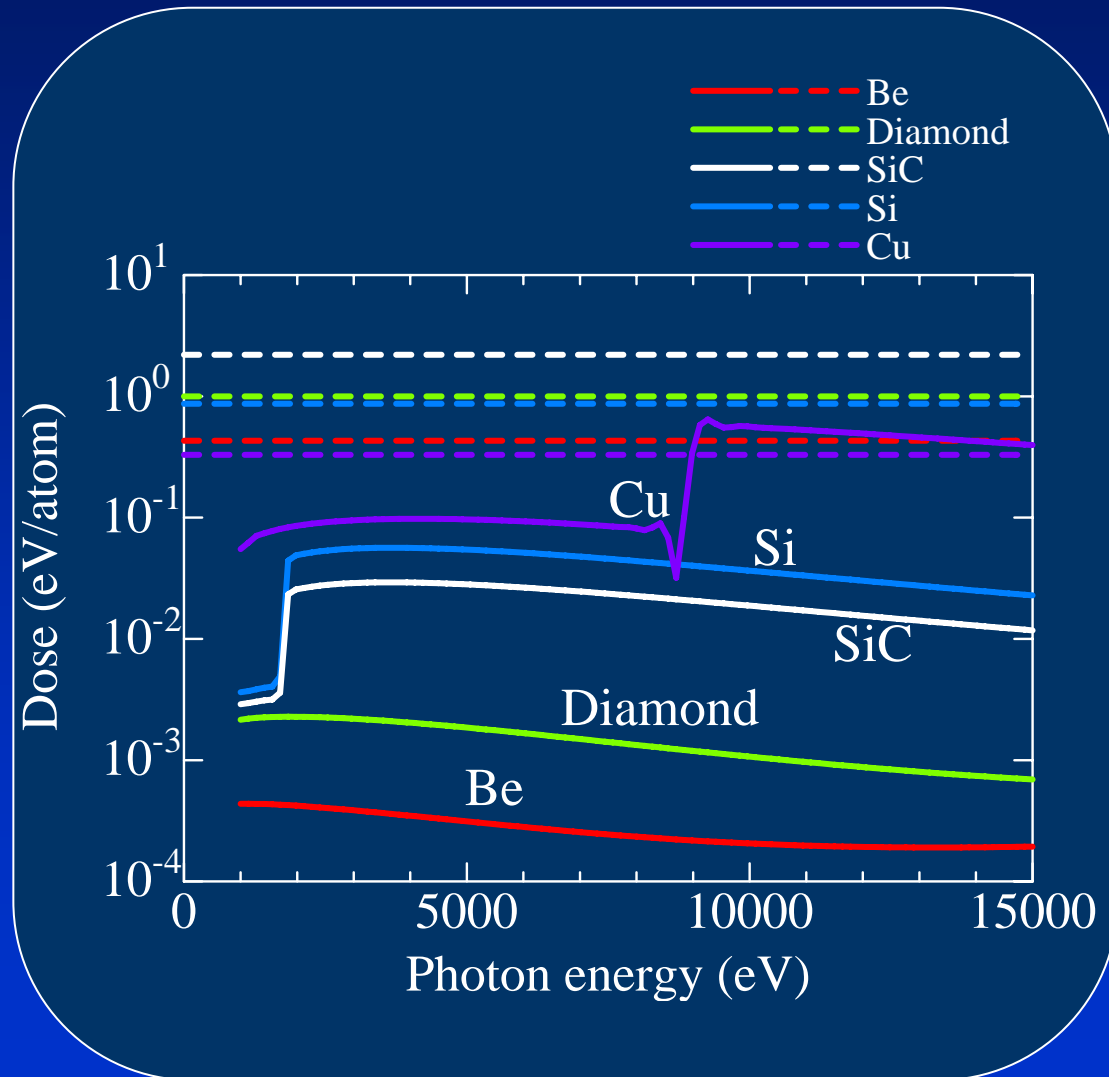
Source size: 50 μm ϕ (STD)

Divergence: diffraction limited

e.g. 0.4 μrad (STD)

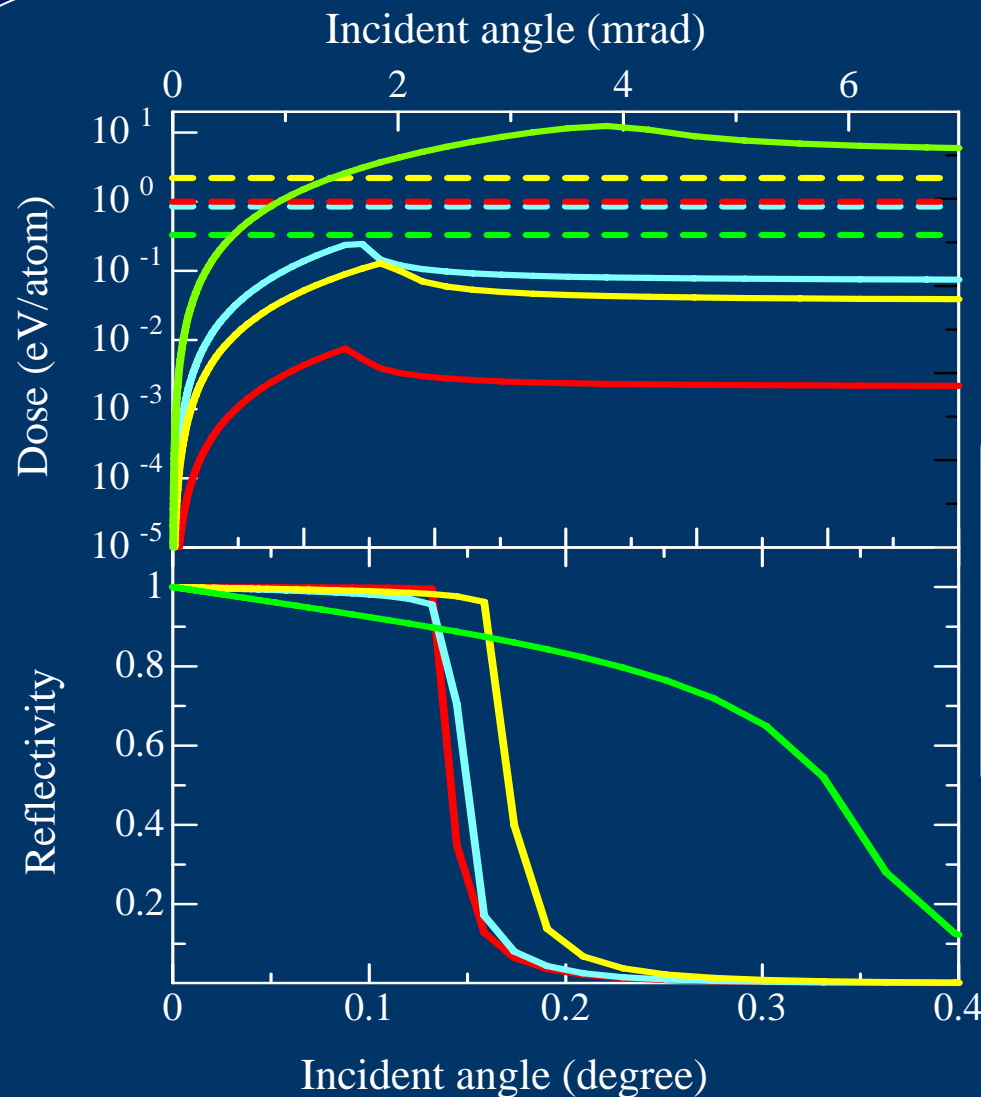
@ $E=12.4$ keV

Distance: 100 m



Diamond, Be is OK
Si would be tolerable

Dose for grazing incidence



— C
— SiC
— Si
— Au

Parameters:
7.6e11 photons/pls
Source size: 50 μm ϕ (STD)
Divergence: diffraction limited
e.g. 0.4 μrad (STD)
@ $E=12.4$ keV
Distance: 100 m

C, SiC would be OK
Si ??

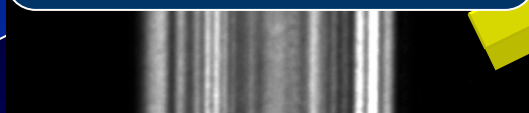
Photon Optics for XFEL



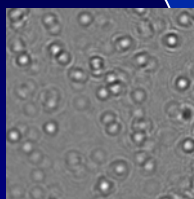
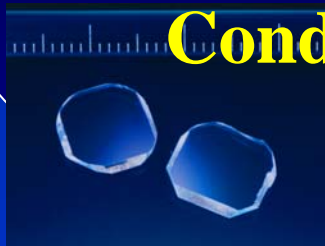
XFEL



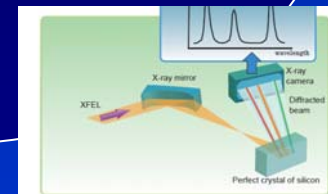
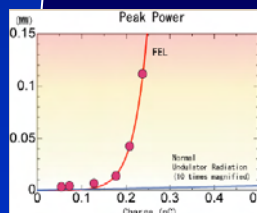
**Dose
Spatial coherence**



**Photon Beam
Conditioning**



**Photon Beam
Diagnostics**



3rd gen. SR



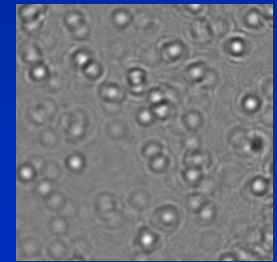
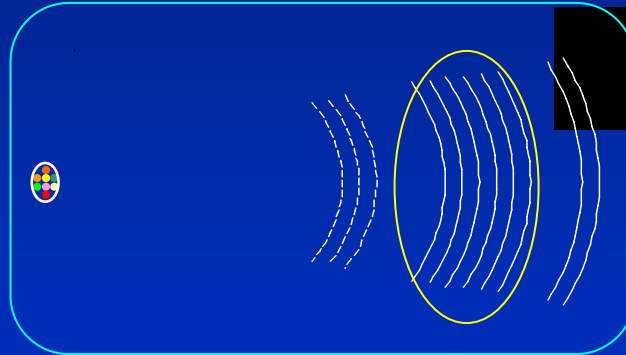
VUV FEL



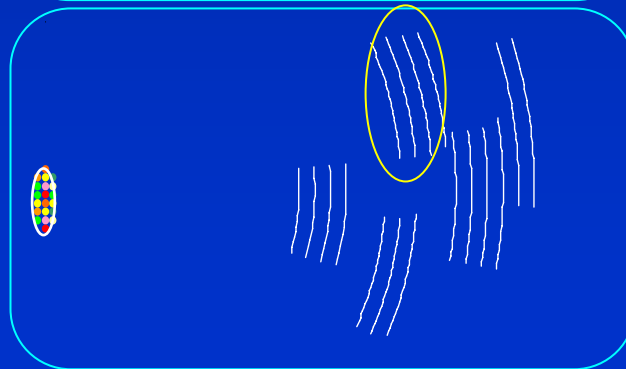
Wave field

Coherent illumination:
Bulk and **surface** quality to avoid speckles

SASE-FEL



SR



SPring-8

SPring-8 (1436 m)
since 1997

1km BL
since 2000



Mirror: SP8 - Osaka Univ. collaboration

Mirror: Silicon (001) / Incident angle 1.2 mrad / Mirror length 100 mm

Camera distance:

Premachined

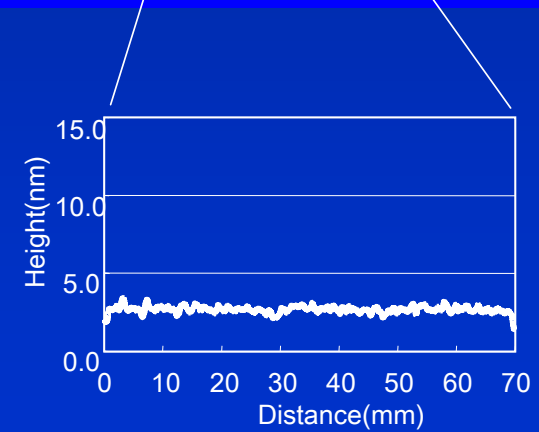
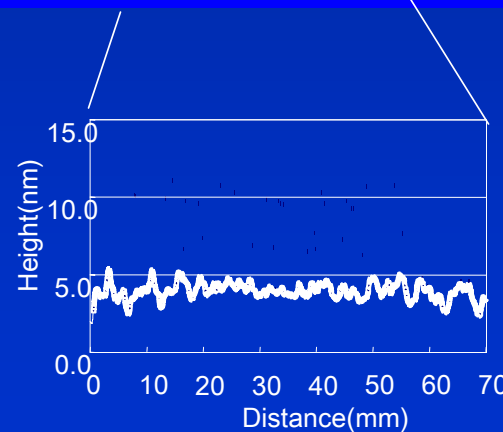
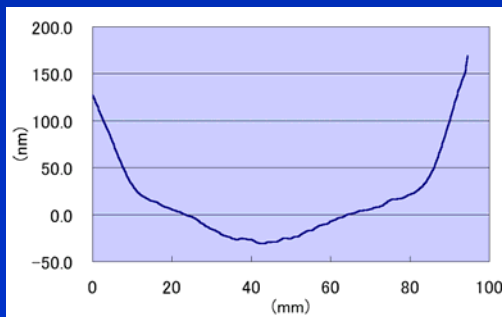
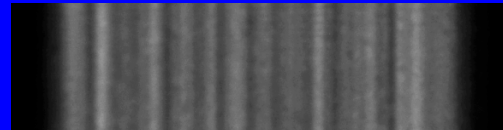
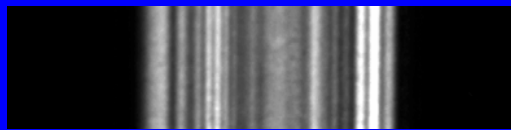
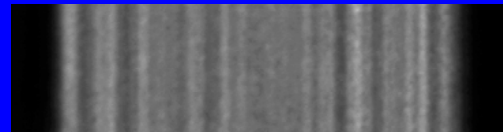
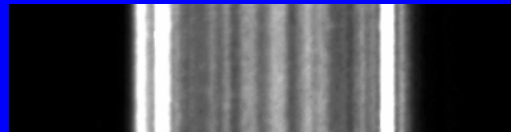
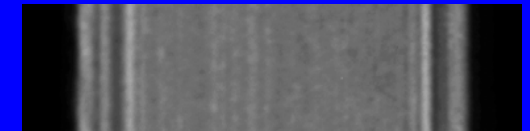
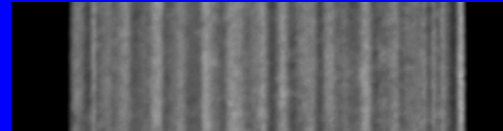
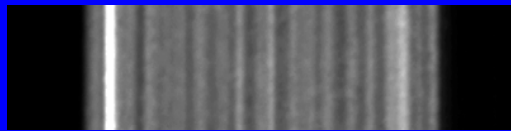
PCVM

PCVM+EEM

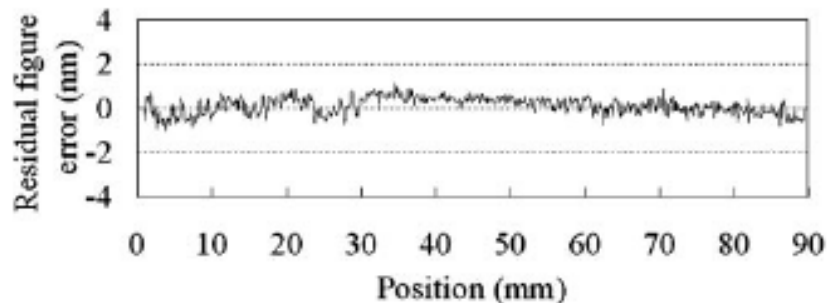
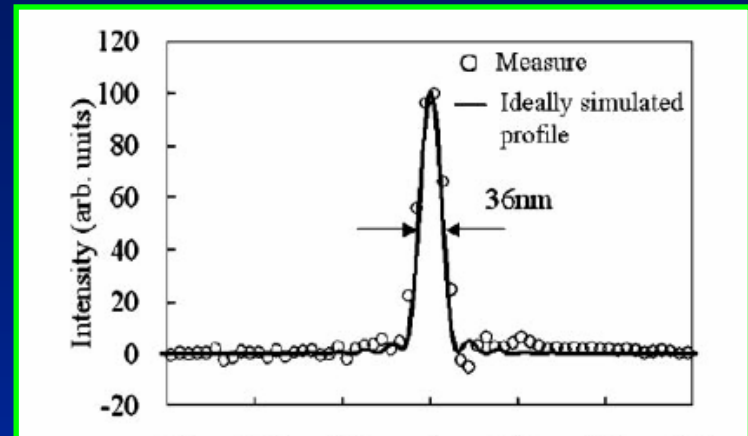
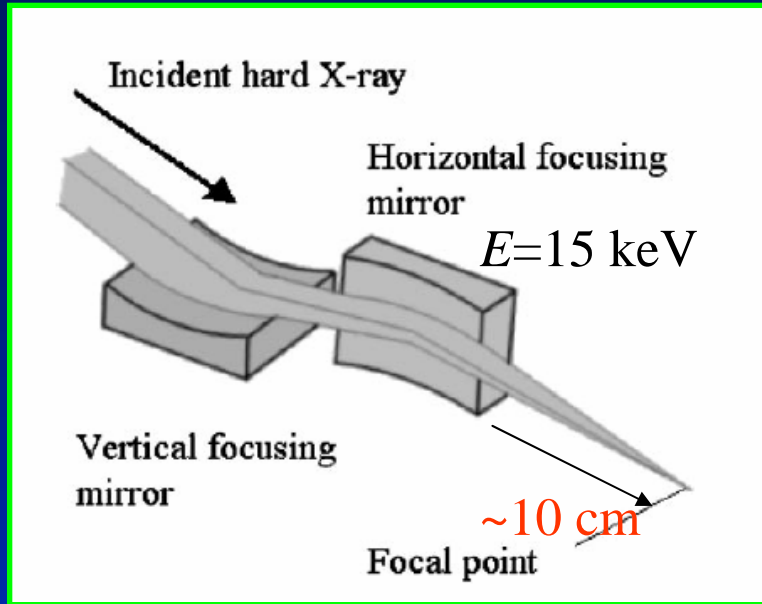
166 mm

566 mm

966 mm



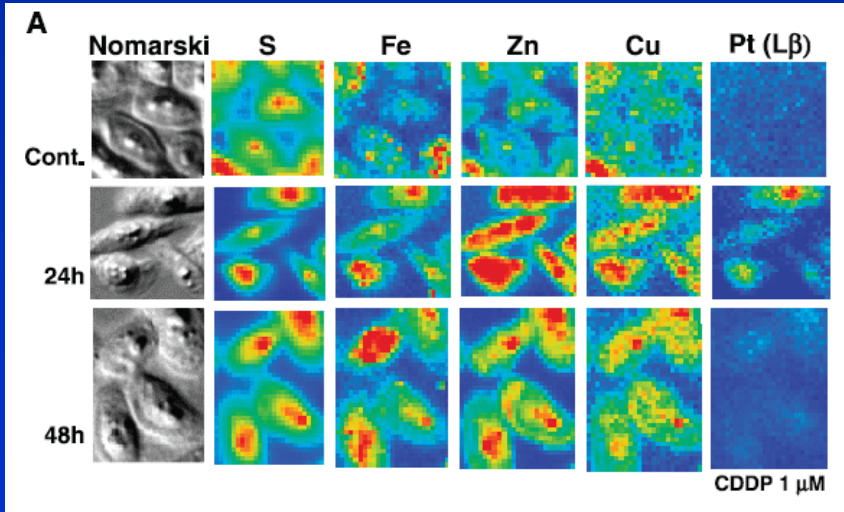
Nano focusing



accuracy of 2 nm along whole surface

Fig. 2. (a) Figure profiles and (b) horizontal and (c) vertical focusing mirror reflective surface residual figure error profiles. The surfaces of the mirrors were figured such that the measured profiles are transformed into the designed surfaces. An unprecedentedly accurate surface of approximately 2 nm in peak to valley height was achieved on both mirror surfaces.

Mimura et al., JJAP, 44 (2005) L539



Shimura et al., Cancer Research, 65 (2005) 4998

$$10 \text{ GW}/(10 \text{ nm})^2 = 1e21 \text{ W/cm}^2$$

Monochromator

Bandwidth $\Delta E/E$

XFEL : $6e-4$

Silicon : $1e-4$ with (111)

Diamond: $6e-5$ with (111)

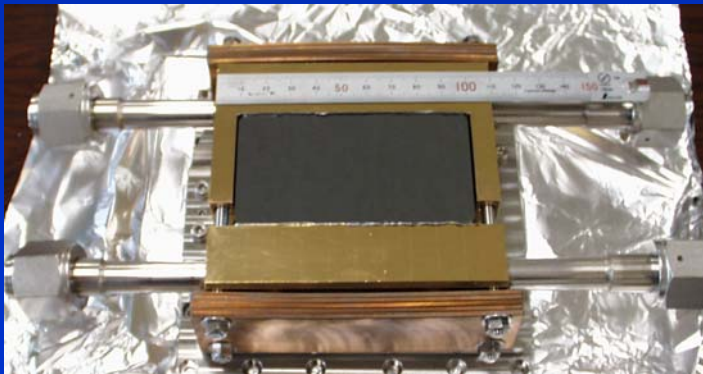
$8e-9$ with (11 5 3)

K. Tamasaku et al., J Phys. D **38** (2005) A61

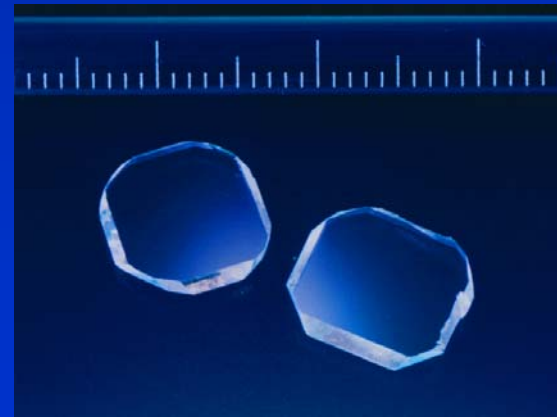
Yabashi et al., RSI **72** (2001) 4080

Yabashi et al., PRL **87** (2001) 140801; PRL **88** (2002) 244801

Single-crystal silicon
with cooling holder

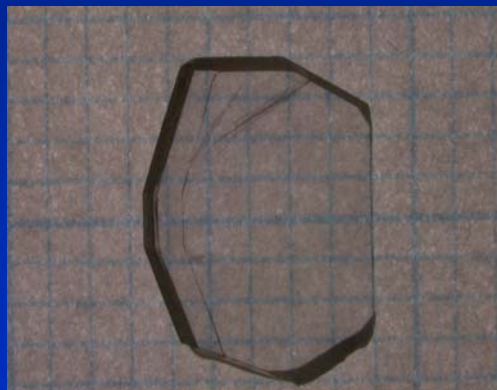


Single-crystal diamond: Type IIa
Collaborated with
Sumitomo Electric Industry

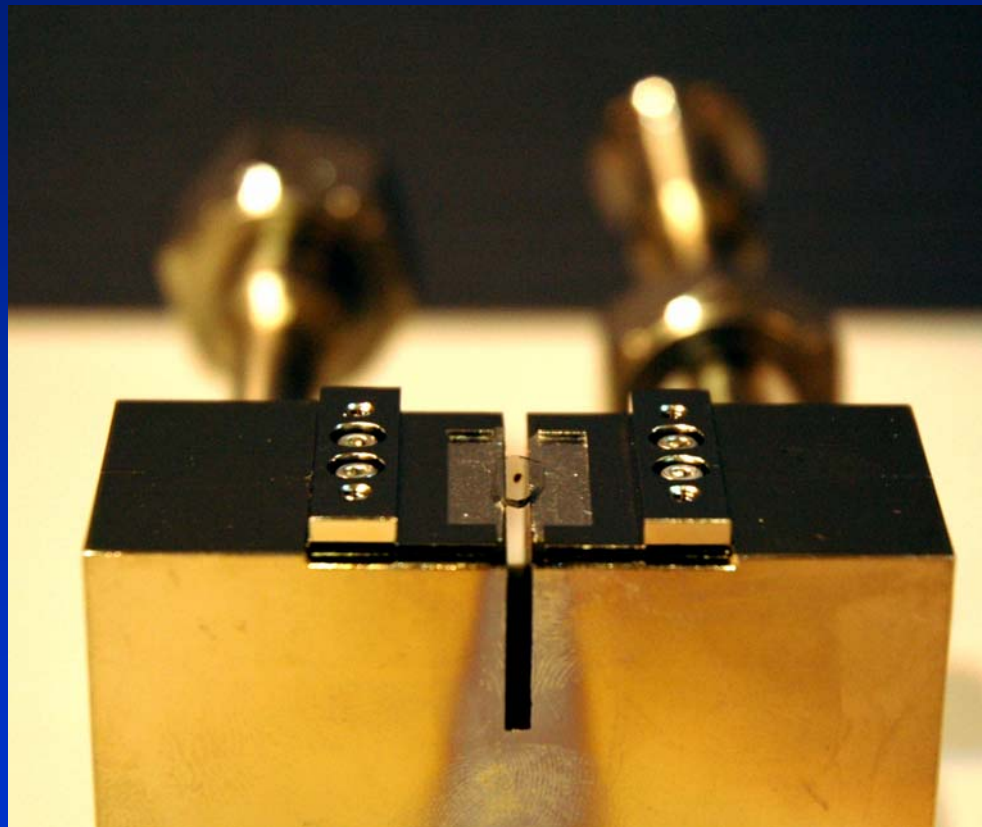


Diamond monochromator

(111)



5 mm



Diamond attached on Cu holder

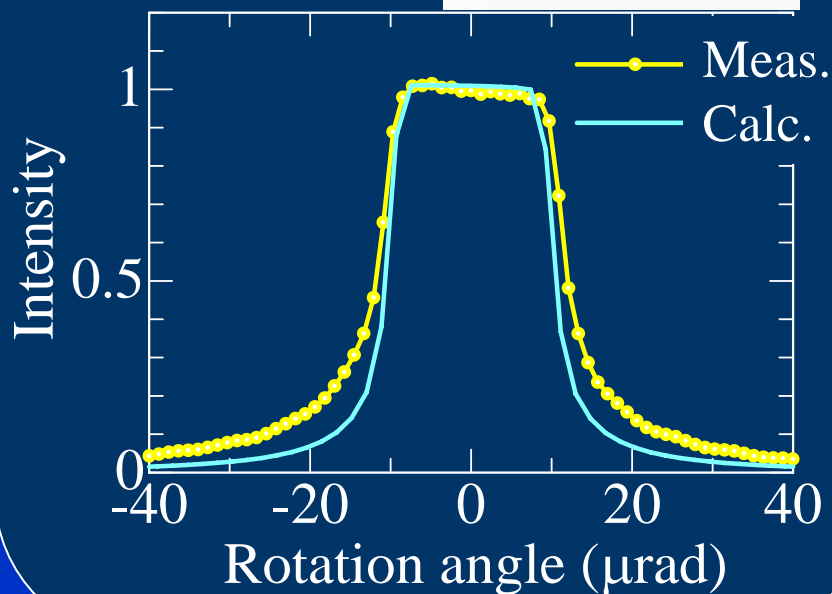
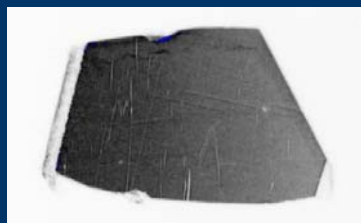
Diamond monochromator

M. Yabashi et al., Proc. SRI 2006 (in press)

(111) polished crystals

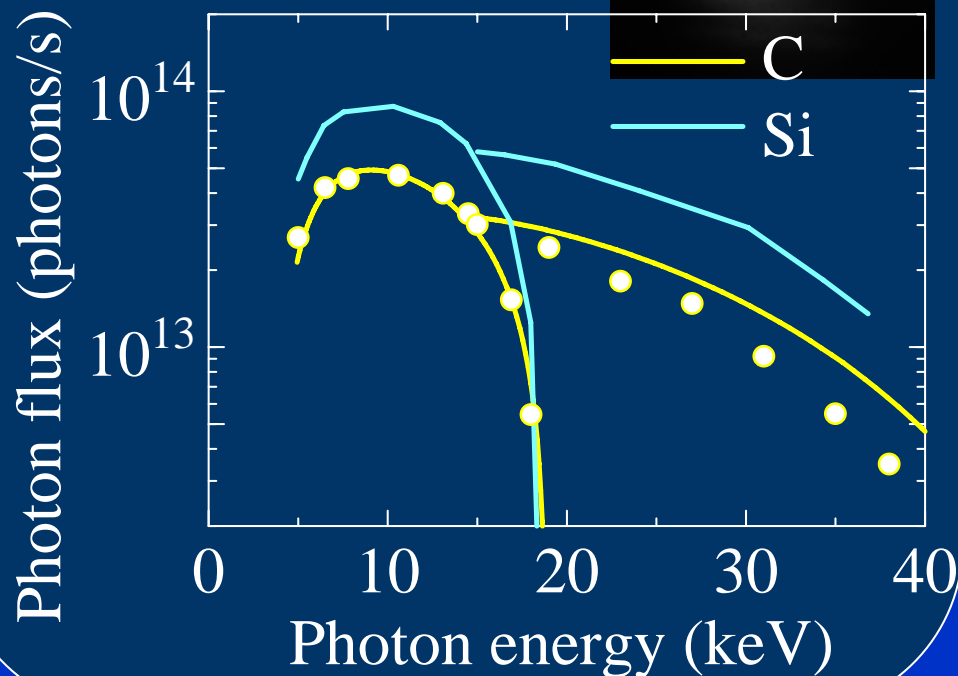
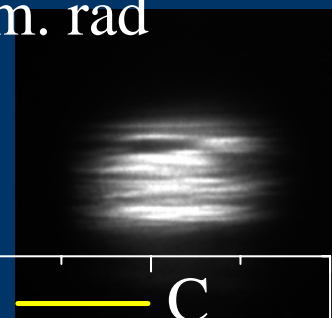
$\sim 8 \times 4 \times 0.4 \text{ mm}^3$

@ 1km BL



$I_b = 100 \text{ mA}$, $\varepsilon = 3 \text{ nm. rad}$

@ BL39XU



Surface polish is required for improving image quality

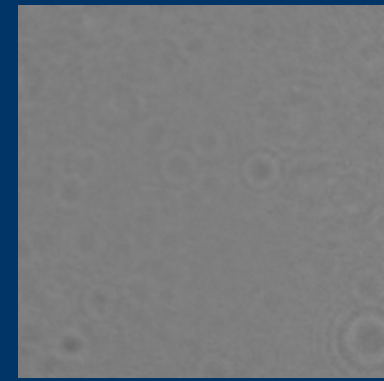
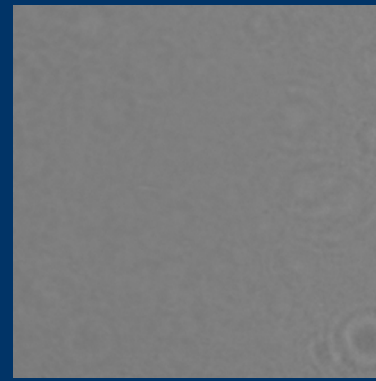
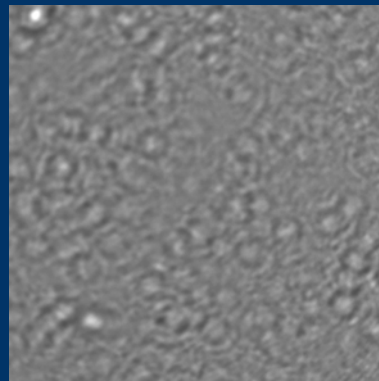
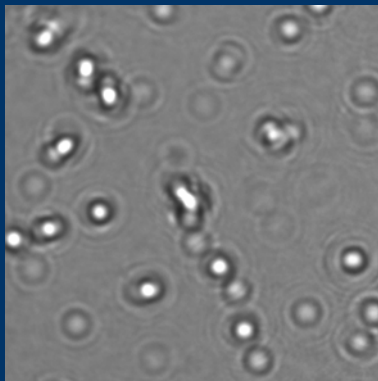
Be window

S. Goto et al., AIP conf. proc. **705** (2004) 405;

S. Goto et al., Proc. SRI 2006 (in press)

@ 1-km beamline (29XU), $E=12.4$ keV, $d= 1400$ mm

100 μm



Polished O-30
(HIP powder foil)
100 nm p-v

Polished IF-1
(Ingot foil)
100 nm p-v

Polished PVD
50 nm p-v

Kapton

Summary

- XFEL construction
 - Machine scale is now being finalized
 - Construction of machine building will be started in 2007
 - User operation of test accelerator will be started in 2007
- X-ray optics
 - Dose issue: need further study (& collaboration), especially for mirror and low-energy optics
 - Mirror: speckleless plane mirror & diffraction limited focusing
 - Diamond: Flux OK, Image need to more development
 - BeW: Polished PVD OK

